



# **TSMC TECHNOLOGY OPTIONS**

## Common flow for 28 nm and 65 nm mini@sic

We see an increased interest in the TSMC 28 nm and 65 nm mini@sic.To optimise the number of designs on the mini@sic runs, we have defined a **common process flow** shown below. Supporting different process flows for all customer designs is not possible.

If you are planning to use any different process flow than shown in the two tables below, please take into account that your design may end up on the waiting list, and in the worst case, it may be postponed to the next mini@sic run.

### Recommended 28 nm mini@sic options

Metal Scheme	9M_5XIYIZIU UT-ALRDL		
Flip-Chip/bumping	Not supported in the common flow. Please contact eptsmc@imec.be.		
Allowed devices	<ul> <li>(1) ultra low Vt = {VTUL_N OR VTUL_P}</li> <li>(2) low Vt = {VTL_N OR VTL_P}</li> <li>(3) high Vt {VTH_N OR VTH_P}</li> <li>(4) ultra high Vt = {UHVT_N OR UHVT_P}</li> <li>Standard devices are by default allowed</li> <li>Contact eptsmc@imec.be if other Vt's are needed.</li> </ul>		
SRAM/ ULL SRAM	Not supported in the common flow. Please contact <a href="mailto:epistemec.be">epistemec.be</a> .		
AP thickness	28kA		
Backlapping thickness	11 mils		
Chip size	The height of the layout (Y-dimension) should be fixed: Imm, I.5mm, 2 mm or 2.5mm. The X-dimension of the layout is not fixed (minimum Imm).		

#### Important note:

Always use the T-N28-CR-SP-029 (mmWave ULL) PDK with flavor RF HPC+ 0.9/1.8V. Sub-dicing of multiple sub-chips is not possible.

### Recommended 65 nm mini@sic options

Metal Scheme	Ip9m_6x1z1u_MIM_APRDL		
Flip-Chip/bumping	Not supported in the common flow. Please contact <u>eptsmc@imec.be</u> .		
AP thickness	14kA		
MIM Value	2fF/um2		
Backlapping thickness	11 mils		
Chip size	The height of the layout (Y-dimension) should be fixed: Imm, 1.5mm or 2 mm. The X-dimension of the layout is not fixed (minimum Imm).		

#### Important note:

No deviation possible from MS/RF LP flavor with 1.2V core and 2.5V IO. Sub-dicing of multiple sub-chips is not possible.





# Full list of mini@sic options

Options mini@sic Runs	ю	Core	Remarks
TSMC 0.13µm CMOS High Voltage Mixed Signal based, Low Power, BCD Plus Triple Gate 1.5/3.3/5/10/12/16/20/24/28/36/VG1.5/3.3/5VV	3.3/5V	1.5V	0.13µm BCD/BCD+ MiM Capacitor 1.0fF/µm2: Only offered at FAB12
TSMC 65nm CMOS Mixed-Signal/RF, Low Power	2.5V (1.8UD, 3.3OD)	1.2V	
TSMC 40nm CMOS Mixed-Signal/RF, Low Power	2.5V (1.8UD, 3.3OD)	1.IV	Triple gate oxide not supported
TSMC 28nm CMOS RF HPC (+)	1.8V	0.9V	
TSMC 16nm RF FinFET Compact	1.8V	0.8V	

#### Important note:

Contact <u>eptsmc@imec.be</u> if any of the following options are used: Bumping, MTP/OTP, Deep Trench, High Linearity MiM, Schottky Barrier Diode, ULL N/PMOS. The metal scheme can be chosen from the list below to ensure all verification and extraction (RC) decks are available.

Technology	Metalization	Topmetal Mz/Mn	Topmetal Mu	
0.13µm HV BCD Plus	6M	lp6m_4x1n_alrdl	/	
65 LP	6M	lp6m_4x1z_mim_alrdl	lp6m_3xlzlu_mim_alrdl	
			lp6m_4xlu_mim_alrdl	
	7M	lp7m_4x2z_mim_alrdl	lp7m_4xlzlu_mim_alrdl	
		lp7m_5x1z_mim_alrdl	lp7m_4x1z1u_mim_ut-alrdl	
			lp7m_5xlu_alrdl	
	8M	1		
	9M	lp9m_6x2z_mim_alrdl	lp9m_6xlzlu_mim_alrdl	
			lp9m_6xlzlu_mim_ut-alrdl	
40 LP	6M	lp6m_3x2z_alrdl	/	
		lp6m_4x1z_alrdl		
	7M	lp7m_4x2z_alrdl	lp7m_4x1z1u_alrdl	
		lp7m_5x1z_alrdl	lp7m_4xlzlu_ut-alrdl	
	8M	lp8m_5x2z_alrdl	lp8m_5x1z1u_alrdl	
		lp8m_5x2z_ut-alrdl	lp8m_5xlzlu_ut-alrdl	
		lp8m_6x1z_alrdl		
	9M	lp9m_6x2z_alrdl	/	
		lp9m_6x2z_ut-alrdl		
		lp9m_7x1z_alrdl		
	10M	lpl0m_7x2z_alrdl	lpl0m_7xlzlu_alrdl	
28 HPC+ (use MMWAVE PDK)	7M	lp7m_4xlylz_alrdl	/	
	8M	lp8m_5x2r_alrdl	lp8m_5xlzlu_ut-alrdl	
		lp8m_5x2r_ut-alrdl		
	9M	1	lp9m_5xlylzlu_ut-alrdl_	
16nm RF FinFET Compact	9M	/	IP9M_2XA1XD3XE1Z1U_UT AIRDL	

Important note: alrdl = 14kA, ut-alrdl = 28kA

### **Metal stacks**